

Amendment to the Claims

1. (Currently Amended) An apparatus for processing a substrate, the apparatus comprising:

a substrate holder for holding and rotating a substrate;

a scattering prevention cup for circumferentially surrounding the substrate held by the substrate holder to prevent a substrate processing liquid supplied to the substrate from being scattered around; and

a scattering prevention cup cleaner for cleaning an inner wall surface of the scattering prevention cup, the scattering prevention cup cleaner including a reverse side nozzle for horizontally supplying a cleaning liquid to the substrate holder in a direction toward the scattering prevention cup, wherein, upon rotation of the substrate holder, the cleaning liquid from the reverse side nozzle cleans an inner wall surface of the scattering prevention cup and an upper surface of the substrate holder.

2. (Original) An apparatus according to claim 1, wherein the scattering prevention cup is vertically movable between a lower substrate transfer position, an upper scattering prevention position, and a cleaning position between the lower substrate transfer position and the upper scattering prevention position.

3. (Original) An apparatus according to claim 1, wherein the scattering prevention cup cleaner is arranged to clean the inner

wall surface of the scattering prevention cup with a cleaning liquid supplied to the substrate.

4-7. (Cancelled)

8. (Currently Amended) A method of processing a substrate, comprising:

processing a substrate with a ~~chemical~~ substrate processing liquid;

simultaneously cleaning at least one of a substrate holder for holding and rotating the substrate, and an inner wall surface of a scattering prevention cup for circumferentially surrounding the substrate held by the substrate holder to prevent a substrate processing liquid supplied to the substrate from being scattered around, the substrate holder and the inner wall surface of the scattering prevention cup being cleaned by horizontally supplying a cleaning liquid from a reverse side nozzle to a surface of the substrate holder while rotating the substrate holder, and a processing liquid supply portion for supplying a substrate processing liquid to the substrate held by the substrate holder;
and then

cleaning the substrate which has been processed by the chemical liquid.

9. (New) An apparatus according to claim 1, wherein the substrate holder cleaner comprises a second reverse side nozzle for supplying chemical and cleaning liquids in a vertical direction to the reverse side of the substrate held by the substrate holder.

10. (New) An apparatus according to claim 9, further comprising a cleaning liquid supply nozzle mounted on an upper end of the scattering prevention cup for supplying a cleaning liquid radially inwardly of the substrate holder.

11. (New) An apparatus according to claim 9, further comprising first cleaning liquid supply nozzle located above and laterally outwardly of the substrate holder for supplying cleaning liquid onto an upper surface of the substrate held by the substrate holder, and a second cleaning liquid supply nozzle mounted on an upper end of the scattering prevention cup for supplying a cleaning liquid radially inwardly of the substrate holder.

12. (New) An apparatus according to claim 1, further comprising a plurality of cleaning liquid supply nozzles disposed above the scattering prevention cup.